Supplementary Information

Vertical Al₂Se₃/MoSe₂ Heterojunction on Sapphire

Synthesized by Using Ion Beam

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Calculations

In Fig. S2a, the length of the dashed line, which contains a quadruple reciprocal vector, is equal to 8.933 nm⁻¹, so that the length of the reciprocal vector is 2.233 nm⁻¹. The inverse of 2.233 nm⁻¹ is equal to 0.4478 nm that corresponds to the (011) interplanar distance (0.4587 nm) of Al₂Se₃. On the other hand, the length (16.591 nm⁻¹) of the dashed line as shown in Fig. S2b contains a quadruple reciprocal vector. Hence, the length of the reciprocal vector is 4.148 nm⁻¹. The inverse of 4.148 nm⁻¹ is equal to 0.241 nm that corresponds to the (400) interplanar distance (0.25 nm) of Al₂Se₃. These calculations, which derived from the experimental results, are in agreement with the theory and the error rate is less than 5%, indicating that the results are believable.



Fig. S1 (a) STEM dark-field image of the $MoSe_2/Al_2Se_3$ /sapphire layer structure. (b) Depth concentration distribution of Mo, Se, and Al.



Fig. S2 (a) The distance between (011) reciprocal points of Al_2Se_3 . (b) The distance between (400) reciprocal points of Al_2Se_3 .



Fig. S3 (a) The top-view SEM image of pristine sapphire. (b) The top-view SEM image of Mo film on sapphire. (c) The tilt-view SEM image of the patterned $MoSe_2/Al_2Se_3$ on sapphire. (d) The EDS spectrum of the area corresponding to the rectangle in (c).